	Application No.	Applicant(s)	
	10/728,842	SILVERBROOK, KIA	(BU)
Notice of Allowability	Examiner	Art Unit	
	Huan H. Tran	2861	
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGOT (of the Office or upon petition by the applicant. See 37 CFR 1.313	ars on the cover sheet with OR REMAINS) CLOSED in the or other appropriate communing GHTS. This application is subtant MPEP 1308.	the correspondence address his application. If not included ication will be mailed in due cours	
2. The allowed claim(s) is/are 1-40.			
 3. ☐ The drawings filed on <u>08 December 2003</u> are accepted by 	the Examiner.		
4. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" on the other to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submited in INFORMAL PATENT APPLICATION (PTO-152) which give (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the position of the deposit attached Examiner's comment regarding REQUIREMENT In the deposit of the deposit of the priority documents and	been received. been received in Application cuments have been received in Application cuments have been received in this communication to file and ENT of this application. Itted. Note the attached EXAM is reason(s) why the oath or do to be submitted. It be submitted. It is application in the submitted in th	No In this national stage application for this national stage application for the requirer of the complying with the requirer of the complex of the Office action of the Office action of the the the complex of the complex of the complex of the complex of the the complex of the complex of the complex of the the complex of the co	ments CE OF
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 12/12/03 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	6. ☐ Interview Sur Paper No./M 8), 7. ☐ Examiner's A	rmal Patent Application (PTO-152 nmary (PTO-413), ail Date mendment/Comment tatement of Reasons for Allowand Primary Examiner AU 2861	

DETAILED ACTION

Allowable Subject Matter

- 1. Claims 1-40 are allowed.
- 2. The following is an examiner's statement of reasons for allowance: Claims 1 and dependent claims thereof are allowable at least for the reason that prior art of record do not teach or suggest—alone or in any combination—the claimed inkjet printhead having the limitation "wherein, each of the liquid passages is formed by etching a blind hole into the wafer from the drop ejection side, and etching a supply passage from the liquid supply side of the wafer to the hole; such that, the blind hole extends into the wafer passed the drive circuitry; and, the supply passage is etched to a depth that extends passed the blind end of the hole by an overlap greater thanthe sum of the fabrication tolerances of both etch processes".

Claims 11 and dependent claims thereof are allowable at least for the reason that prior art of record do not teach or suggest the claimed method of ejecting drops of an ejectable liquid from an inkjet printhead wherein the inkjet printhead having the limitation "wherein, each of the liquid passages is formed by etching a blind hole into the wafer from the drop ejection side, and etching a supply passage from the liquid supply side of the wafer to the hole; such that, the blind hole extends into the wafer passed the drive circuitry; and, the supply passage is etched to a depth that extends passed the blind end of the hole by an overlap greater than the sum of the fabrication tolerances of both etch processes"

Claims 21 and dependent claims thereof are allowable at least for the reason that prior art of record do not teach or suggest the claimed method of fabricating inkjet printheads which includes the limitation "forming the nozzles, ejection actuators, associated drive circuitry and

Art Unit: 2861

liquid passage on and through the wafer using lithographically masked etching techniques: including, forming each of the liquid passages by etching a blind hole into the wafer from the drop ejection side: filing the hole with resist: etching a supply passage from the liquid supply side of the wafer to the hole and subsequently stripping the resist from the hole; such that, the blind hole extends into the wafer passed the drive circuitry; and, the supply passage is etched to a depth that extends passed the blind end of the hole by an overlap greater than the sum of the fabrication tolerances of both etch processes"

Claim 31 and dependent claims thereof are allowable for the reason that prior art of record do not teach or suggest the claimed printer system incorporating an inkjet printhead comprising at least the limitation "the nozzles, ejection actuators, associated drive circuitry and liquid passage being formed on and through the wafer using lithographically masked etching techniques; wherein, each of the liquid passages is formed by etching a blind hole into the wafer from the drop ejection side, and etching a supply passage from the liquid supply side of the wafer to the hole; such that, the blind hole extends into the wafer passed the drive circuitry; and, the supply passage is etched to a depth that extends passed the blind end of the hole by an overlap geater than the sum of the fabrication tolerances of both etch processes"

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Art Unit: 2861

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Huan H. Tran whose telephone number is (571) 272-2261. The examiner can normally be reached on at work on W-F from 6:30 to 5; T are telework days.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Talbott can be reached on (571) 272-1934. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Huan H. Tran Primary Examiner Art Unit 2861

hht 05/04/05